Physics

NCERT Exemplar Problems

Chapter 14

Semiconductor Electronics

Answers

14.1	(d)
14.2	(b)
14.3	(b)
14.4	(d)
14.5	(b)
14.6	(c)
14.7	(b)
14.8	(c)
14.9	(a), (c)
14.10	(a), (c)
14.11	(b), (c), (d)
14.12	(b), (c)
14 19	(a) (b) (d)

carrier on forming co-valent bonds with Si or Ge.

The size of dopant atoms should be such as not to distort the pure semiconductor lattice structure and yet easily contribute a charge

(i) $10 \times 20 \times 30 \times 10^{-3} = 6V$

(a), (d)

14.16

14.17

14.21

(ii) If dc supply voltage is 5V, the output peak will not exceed
$$V_{cc}$$
 = 5V. Hence, V_0 = 5V.

14.22 No, the extra power required for amplified output is obtained from the

DC source.

readings.

$$hv = \frac{6.6 \times 10^{-34} \times 3 \times 10^8}{6 \times 10^{-7} \times 1.6 \times 10^{-19}} = 2.06 \text{eV}$$
 For the incident radiation to be detected by the photodiode, energy of incident radiation photon should be greater than the band gap.

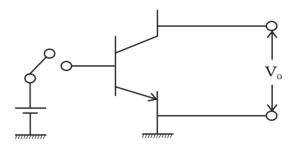
This is true only for D2. Therefore, only D2 will detect this radiation. $I_{B} = \frac{V_{BB} - V_{BE}}{R}$ If R_{I} is increased, I_{B} will decrease. Since $I_{c} = \beta I_{b}$, it will

result in decrease in $I_{\rm C}$ i.e decrease in ammeter and voltmeter

\frac{\frac{1}{2}}{\frac{1}{2}}

OR gate gives output according to the truth table.

A	В	С
0	О	0
0	1	1
1	0	1
1	1	1



Input	Output
A	A
0	1
1	0

4.28 Elemental semiconductor's band-gap is such that emissions are in IR region.

4.29 Truth table

A	В	Y
0	0	0
0	1	0
1	0	0
1	1	1

AND Gate

$$R_{\rm S}=rac{V_{
m S}-V_{
m Z}}{I_{
m Z\,max}}=rac{2}{0.2}=10\,\Omega.$$

14.31 I_3 is zero as the diode in that branch is reverse bised. Resistance in the branch AB and EF are each $(125 + 25)\Omega = 150\Omega$.

As AB and EF are identical parallel branches, their effective resistance is $\frac{150}{2}$ = 75Ω

∴ Net resistance in the circuit =
$$(75 + 25) \Omega = 100 \Omega$$
.
∴ Current $I_1 = \frac{5}{100} = 0.05 A$.

As resistances of AB and EF are equal, and
$$I_1$$
 = I_2 + I_3 + I_4 , I_3 = 0

As resistances of AB and EF are equal, and
$$I_1 = I_2 + I_3 + I_4$$
, $I_3 = 1$.
$$\therefore I_2 = I_4 = \frac{0.05}{2} = 0.025 \text{A}$$

As
$$V_{be} = 0$$
, potential drop across R_b is 10V.

$$\therefore I_b = \frac{10}{400 \times 10^3} = 25 \mu A$$
 Since $V_{ce} = 0$, potential drop across R_c , i.e. $I_c R_c$ is 10V.

$$I_c = \frac{10}{3 \times 10^3} = 3.33 \times 10^{-3} = 3.33 \text{mA}.$$

$$\beta = \frac{I_c}{I_b} = \frac{3.33 \times 10^{-3}}{25 \times 10^{-6}} = 1.33 \times 10^2 = 133.$$

A

B

C₁

C₁

C₁

C₁

D

1

2

3

4

5

5

C₁

C₁

C₁

C₂

C₃

C₄

C₁

C₁

C₃

C₄

C₅

C₁

C₁

C₁

C₁

C₁

C₁

C₁

C₂

C₃

C₄

C₅

C₁

C₁

C₁

C₂

C₃

C₄

C₅

C₁

C₁

C₁

C₂

C₃

C₄

C₅

C₆

C₇

C₈

C₈

C₉

14.33

 \mathbb{C}_2

$$R_c = \frac{V_{CC} - V_{CE}}{I_C}$$

$$R_c = \frac{16 - 8}{4 \times 10^{-3}} = 2 \text{K}\Omega$$

Since,

$$V_{BB} = I_B R_B + V_{BE}$$

$$R_B = \frac{16 - 0.7}{30 \times 10^{-6}} = 510 \text{K}\Omega$$

Now,
$$\beta = \frac{I_C}{I_B} = \frac{4 \times 10^{-3}}{30 \times 10^{-6}} = 133$$

Voltage gain =
$$A_V = -\beta \frac{R_C}{R_B}$$

$$= -133 \times \frac{2 \times 10^3}{510 \times 10^3}$$

$$= 0.52$$

Power Gain = $A_p = \beta \times A_V$

$$= -\beta^2 \frac{R_C}{R_R}$$

$$=(133)^2 \times \frac{2 \times 10^3}{510 \times 10^3} = 69$$

14.35 When input voltage is greater than 5V, diode is conducting

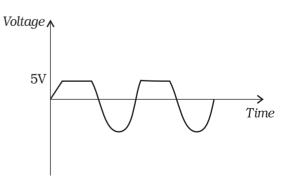
When input is less than 5V, diode is open circuit

14.36 (i) In 'n' region; number of e^- is due to As:

$$n_e = N_D = 1 \times 10^{-6} \times 5 \times 10^{28} \text{ atoms/m}^3$$

$$n_e = 5 \times 10^{22} / \text{m}^3$$

The minority carriers (hole) is



 $n_h = N_A = 200 \times 10^{-6} \times 5 \times 10^{28}$ $= 1 \times 10^{25} / \text{m}^3$

 $n_{\rm b} = 0.45 \times 10/{\rm m}^3$

This is far greater than e^- that existed in 'n' type wafer on which Boron was diffused. Therefore, minority carriers in created 'p' region

(ii) Thus, when reverse biased $0.45 \times 10^{10}/\text{m}^3$, holes of 'n' region would contribute more to the reverse saturation current than 2.25

Similarly, when Boron is implanted a 'p' type is created with holes

$$n_e = \frac{n_i^2}{n_h} = \frac{2.25 \times 10^{32}}{1 \times 10^{25}}$$
$$= 2.25 \times 10^7 / \text{m}^3$$

$$n_h = 1 \times 10^{25}$$

 \times 10⁷/m³ minority e⁻ of p type region.

4.38
$$1 \text{K}\Omega_{\text{ML}}$$

$$I_C \approx I_E :: I_C (R_C + R_E) + V_{CE} = 12 \text{ V}$$

 $R_E = 9 - R_C = 1.2 \text{ K}\Omega$

$$V_B = V_E + V_{BE} = 1.7 \text{ V}$$

$$I = \frac{V_B}{20 \text{ K}} = 0.085 \text{ mA}$$

$$R_B = \frac{12-1.7}{I_C / \beta + 0.085} = \frac{10.3}{0.01+1.085} = 108 \text{ K}\Omega$$

14.40
$$I_E = I_C + I_B$$
 $I_C = \beta I_B$ (1)

$$I_{c}R_{c} + V_{cF} + I_{F}R_{F} = V_{cC} \tag{2}$$

$$RI_{R} + V_{RF} + I_{F}R_{F} = V_{CC} \tag{3}$$

From (3) $I_e \approx I_C = \beta I_B$

$$(R + \beta R_E) = V_{CC} - V_{BE}, \quad I_B = \frac{V_{CC} - V_{BE}}{R + \beta R_E} = \frac{11.5}{200} \text{ mA}$$

From (2)

$$\begin{split} R_{C} + R_{E} &= \frac{V_{CC} - V_{CE}}{I_{C}} = \frac{V_{CC} - V_{CE}}{\beta I_{B}} = \frac{2}{11.5} (12 - 3) \text{K}\Omega = 1.56 \text{K}\Omega \\ R_{C} &= 1.56 - 1 = 0.56 \text{K}\Omega \end{split}$$